



YOUR MANUFACTURING  
PARTNER FOR  
CVD COATING SERVICE

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## IMERYS GRAPHITE & CARBON CVD COATING SERVICE

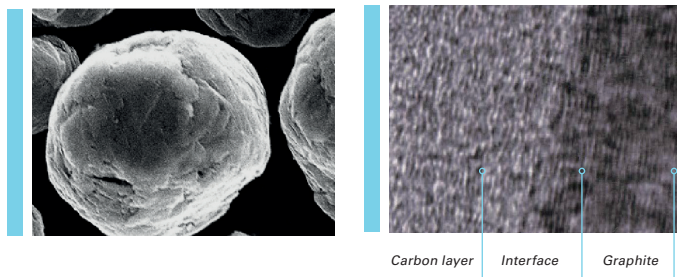
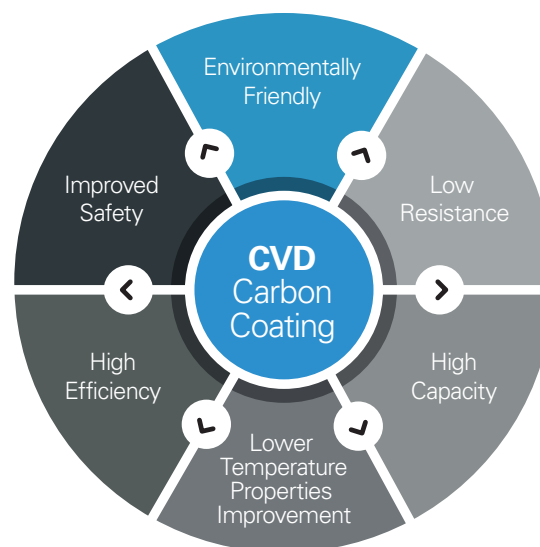
### YOUR MANUFACTURING PARTNER IN CVD CARBON COATING

Imerys Graphite & Carbon chemical vapor deposition (CVD) coating is a unique one-of-a-kind technology that is applicable to various substrates (carbon and non-carbon based), resulting in improved performance for various applications.

### BENEFITS OF OUR CVD CARBON COATING

- ✓ **Better thickness** control of the carbon layer compared to other technologies
- ✓ **Improved particle surface properties**, resulting in:
  - Smoother surface
  - Better electrical conductivity
  - Better thermal conductivity
  - Better mixing compatibility with other materials
- ✓ **Reduced CO<sub>2</sub> footprint** compared to other technologies

### EXAMPLE: BENEFITS TO ANODE MATERIALS FOR LI-ION BATTERIES



### EXPERIENCE AND KNOWLEDGE TO DEVELOP YOUR PRODUCTS

Imerys Graphite & Carbon is uniquely positioned to offer the highest level of services, with decades of experience in carbon coating on an industrial scale and a vast portfolio of carbon and non-carbon based materials.

Imerys Graphite & Carbon values close cooperation with its Customers and you can be assured that all requests are treated confidentially. With designated facilities capable of kilogramme sized to kilotonne sized operations, our plant in Kitakyushu, Japan can meet your demands, both in terms of product development support and in industrial scale mass production. Our Toll Processing Services offer state of the art analytical testing and quality control facilities to fully characterize raw materials and final product. Modern, fully equipped specialised application laboratories serving different markets are available to characterize the performance of the final product.

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